

IN THE CLAIMS:

Please cancel Claims 19 - 23 and 25 without prejudice.

1. (Previously Presented) An apparatus for depositing at least one thin film on a substrate useful in electronic applications, the apparatus comprising:

(a) an in-line continuously moving web for simultaneously transporting a number of substrates to which a thin film of material is to be applied, wherein said moving web is a roll-to-roll moving disposable web consisting essentially of a polymeric material and wherein said substrates are held to said web by friction against or electrostatic attraction to a web surface;

(b) a central processing chamber which is maintained under vacuum and through which at least a portion of said continuously moving web travels;

(c) at least one deposition device which is located within said central processing chamber, where at least a portion of said continuously moving web is exposed to material deposited from said deposition device;

(d) a first moving platform which moves in an x direction and a y direction, which transfers a substrate onto said continuously moving web; and

(e) a second moving platform which moves in an x direction and a y direction, which transfers a substrate from said continuously moving web.

2. (Cancelled)

3. (Cancelled)

4. (Previously Presented) The apparatus of Claim 1, wherein at least one deposition device is a sputtering device.

5. (Previously Presented) The apparatus of Claim 1, wherein a device is present which permits web splicing during continuous operation of said apparatus.

6. (Cancelled)

7. (Previously Presented) The apparatus of Claim 1, wherein said polymeric material is PET.

8. (Original) The apparatus of Claim 4, wherein a power applied to a cathode in said sputtering device is RF power.

9. (Original) The apparatus of Claim 8, wherein said cathode is a sputtering target.

10. (Original) The apparatus of Claim 9, wherein a sputtering target used in said sputtering device is rectangular in shape.

11. (Original) The apparatus of Claim 9, wherein said sputtering target is comprised of a ceramic or metal.

12. (Previously Presented) The apparatus of Claim 11, wherein said sputtering target is comprised of a material having optical transmission properties useful in optical applications.

13. (Original) The apparatus of Claim 4, wherein said sputtering target sputtering device includes a planar magnetron.

14. (Previously Presented) The apparatus of Claim 1, wherein at least one isolating shield is used to separate one thin film deposition area from another thin film deposition area.

15. (Previously Presented) The apparatus of Claim 1, wherein at least said first or said second moving platform is located within a plenum chamber which is at a pressure which is different from the pressure in said central processing chamber.

16. (Previously Presented) The apparatus of Claim 1, wherein said central processing chamber is maintained at a base vacuum of at least 10^{-5} Torr (1.3×10^{-3} Pa).

17. (Previously Presented) The apparatus of Claim 1, wherein said apparatus also includes a cooling surface which permits the cooling of said continuously moving disposable web within said central processing chamber.

18 - 25. (Cancelled)

26. (Previously Presented) The apparatus of Claim 1, wherein said disposable web material is polyvinylidene chloride.